

Title (en)

Electrolytic bath for the deposition of thin layers of pure gold.

Title (de)

Elektrolytisches Bad für das Abscheiden dünner Schichten reinen Goldes.

Title (fr)

Bain électrolytique pour le dépôt de couches minces d'or pur.

Publication

**EP 0149830 A2 19850731 (FR)**

Application

**EP 84115879 A 19841220**

Priority

CH 696183 A 19831229

Abstract (en)

1. Electrolytic bath for the deposit of thin layers of pure gold on passive surfaces, containing from 0.5 to 20 g/l of gold under the form of a gold cyanide of alkali metal, in which gold is trivalent, and at least an acid which is present in a sufficient concentration so as the pH of this bath is at most of 0.4, characterized in that the acid is selected from the group comprising the sulfuric acid, the sulfamic acid, the pyrophosphoric acid, the mono-, di- and tri-chloroacetic acids, the malic acid, and the 1-hydroxy-1, 1-ethylidene-diphosphonic, hydroxy-methylphosphonic and amino-tris(methylene-phosphonic) acids, and the mixtures thereof.

Abstract (fr)

Le bain électrolytique, permettant de déposer des couches minces (environ 0, 5 µ) d'or pur sur des surfaces passives, contient de 0,5 à 20 g/l d'or sous forme d'auricyanure de K ou Na, ainsi qu'un acide ou un mélange d'acides en une quantité telle que le pH du bain soit d'au plus 0,4, et de préférence entre 0,1 et 0,3.

IPC 1-7

**C25D 3/48**

IPC 8 full level

**C25D 3/48** (2006.01)

CPC (source: EP)

**C25D 3/48** (2013.01)

Designated contracting state (EPC)

CH DE FR GB IT LI

DOCDB simple family (publication)

**EP 0149830 A2 19850731; EP 0149830 A3 19861015; EP 0149830 B1 19890405; EP 0149830 B2 19920513;** CH 665656 A5 19880531; DE 149830 T1 19851024; DE 3477588 D1 19890511

DOCDB simple family (application)

**EP 84115879 A 19841220;** CH 696183 A 19831229; DE 3477588 T 19841220; DE 84115879 T 19841220